

Notice of Allowability	Application No.	Applicant(s)
	10/667,517	ODA ET AL.
	Examiner	Art Unit
	Pamela E Perkins	2822
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in this and it is an it is	pplication. If not included on will be mailed in due course. THIS
1. This communication is responsive to the filing of the appli	cation papers on 23 September 200	<u>13</u> .
2. 🔀 The allowed claim(s) is/are <u>1-6</u> .		~
3. 🗵 The drawings filed on 23 September 2003 are accepted b	y the Examiner.	
4. Acknowledgment is made of a claim for foreign priority of a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the priority documents have 4. Copies of the priority documents have 5. Copies of the priority documents have 5. Copies of the priority documents have 6. Copie	re been received. re been received in Application No. 1 recomments have been received in this recomment of this application. Initial Note the attached EXAMINER recomments have attached EXAMINER recomments have reason(s) why the oath or declar recomments be submitted. The son's Patent Drawing Review (PTC) recomment or in the recomment or in the recomment of the draw the header according to 37 CFR 1.121 Disit of BIOLOGICAL MATERIAL	c national stage application from the complying with the requirements R'S AMENDMENT or NOTICE OF cation is deficient. D-948) attached Office action of complying in the front (not the back) of complying with the complex
 Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date 9/23/03 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material 	.6. ☐ Interview Summary Paper No./Mail Da 7. ☑ Examiner's Amend 8. ☑ Examiner's Statem 9. ☐ Other	ate .

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DETAILED ACTION

This office action is in response to the filing of the application papers on 23 September 2003. Claims 1-6 are pending.

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Claim 1 has been amended as follows:

1. A method of making

quantum size effect micro particles, characterized in that it comprises the steps of:

introducing silane into a VHF-band plasma of argon while controlling the time duration in which the silane is so introduced to form Si single crystal micro particles with their particle size controlled;

forming on a substrate a layer of such said Si single crystal micro particles so formed; and

converting respective surface areas of the said Si ingle single crystal macro micro particles in said layer on said substrate into insulating films.

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Allowable Subject Matter

Claims 1-6 are allowed.

Reasons for Allowance

The following is an examiner's statement of reasons for allowance: prior art does not anticipate, teach, or suggest a method of making micro particles where silane is introduced into a VHF-band plasma of argon while controlling the time duration in which the silane is so introduced to form Si single crystal micro particles with their particle size controlled; forming on a substrate a layer of such Si single crystal micro particles so formed; and converting respective surface areas of the Si single crystal macro particles in the layer on the substrate into insulating films.

For example, Tazaki et al. (JP 09-007499) disclose a method of making quantum size effect micro particles where helium and oxygen are introduced while controlling the time duration to form micro particles with their particle size controlled; and forming on a substrate a layer of such the micro particles so formed (constitution). However, Tazaki et al. do not disclose, anticipate, teach, or suggest a method of making quantum size effect micro particles where silane is introduced into a VHF-band plasma of argon and converting respective surface areas of the Si single crystal macro particles in the layer on the substrate into insulating films.

Kuribayashi et al. (6,607,593) disclose a method of making micro particles where a high frequency plasma of argon is used to form Si single crystal micro particles with their particle size controlled (col. 1, lines 22-36; col. 6, lines 31-39). However,

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Kuribayashi et al. do not disclose, anticipate, teach or suggest a method of making quantum size effect micro particles where silane is introduced into a VHF-band plasma of argon while controlling the time duration in which the silane is so introduced to form Si single crystal micro particles with their particle size controlled; forming on a substrate a layer of such Si single crystal micro particles so formed; and converting respective surface areas of the Si single crystal macro particles in the layer on the substrate into insulating films.

The prior art made of record in this action does not anticipate, teach, or suggest a method of making quantum size effect micro particles where silane is introduced into a VHF-band plasma of argon while controlling the time duration in which the silane is so introduced to form Si single crystal micro particles with their particle size controlled; forming on a substrate a layer of such Si single crystal micro particles so formed; and converting respective surface areas of the Si single crystal macro particles in the layer on the substrate into insulating films.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Pamela E Perkins whose telephone number is (571)

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272-1840. The examiner can normally be reached on Monday thru Friday, 9:00am to

5:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Amir Zarabian can be reached on (571) 272-1852. The fax phone number

for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for

published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only.

For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic

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